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## \*BIBDATASHEET\*

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## \* CONTINUATING DATA \*

This application is a CIP of 09/465,811 12/16/1999 ABN

SJL

## \* FOREIGN APPLICATIONS \*

REPUBLIC OF KOREA 98-63793 12/31/1998 SJL

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Foreign Priority claimed 35 USC 119 (d) conditions and Verified and Acknowledged	STATE OR COUNTRY KOREA, REPUBLIC OF	SHEETS DRAWING 2	TOTAL CLAIMS 19	INDEPENDENT CLAIMS 2
<input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> later after  Examiner's Signature SJL	KOREA, REPUBLIC OF	DRAWING 2	19	2

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## TITLE

Cross-linking monomers for photoresist, and process for preparing photoresist polymers using the same

 All Fees

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